

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S102	14	(elo or lateral near2 overgrow\$5) same pitch	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:28
S99	36	S98 and mask\$5 same Gaas	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
S98	477	(kensaku near2 motoki or takuji near2 okahisa or naoki near2 matsumoto).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
S96	41	semiconduct\$6 near4 single near2 crystal\$6 near10 cleav\$6 near10 (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
S92	54	(gan or gallium near2 nitride) near10 (hvpe or (halide or hydride) near5 vapor near2 epitax\$7) near10 (ingot or bulk)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
L5	66	(gan or gallium near2 nitride) near10 (hvpe or (halide or hydride) near5 vapor near2 epitax\$7) near10 (ingot or bulk)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
L4	45	semiconduct\$6 near4 single near2 crystal\$6 near10 cleav\$6 near10 (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
L3	46	L2 and mask\$5 same Gaas	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
L2	512	(kensaku near2 motoki or takuji near2 okahisa or naoki near2 matsumoto).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34
L1	512	(kensaku near2 motoki or takuji near2 okahisa or naoki near2 matsumoto).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:34

S59	7	mask near10 pattern\$6 near10 pitch near10 direction near10 parallel	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:35
S24	195	(stripe mask\$4 or pattern\$6) near15 direction and (gan or gallium near2 nitride) near10 epitax\$7 and (gaas or gallium near2 arsenide) near10 substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:35
L7	235	(stripe mask\$4 or pattern\$6) near15 direction and (gan or gallium near2 nitride) near10 epitax\$7 and (gaas or gallium near2 arsenide) near10 substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:35
L6	9	mask near10 pattern\$6 near10 pitch near10 direction near10 parallel	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/14 01:35